

SEMI Standards – EUV Mask Task Force

San Francisco, California

July 13, 2004

Agenda

1. **Call to Order**
 1. **Introductions**
 2. **Anti-Trust Reminder**
 3. **Intellectual Property Reminder**
 4. **Agenda Review**
2. **Old Business**
 1. **Review of selected material from Feb. 04 EUV Mask Workshop**
 2. **SEMI P37**
3. **New Business**
 1. **IEUVI Mask TWG Issues & Roadmap**
 2. **EUV Mask Data Matrix blue ballot draft**
 3. **EUV Mask Handling Areas blue ballot draft**
4. **Action Item Review**
5. **Review Meeting Schedule**
6. **Adjournment**

Purpose

- **Open discussion of standards work related to EUV masks and supporting technology.**
- **Plan for next workshop.**
 - Nov. '04 @ EUVL Symposium, Japan.
 - Tentative: pre-lim meeting Sept. '04 @ SPIE BACUS.

Critical Issues for EUV Lithography

(October 2003 IEUVI Steering Committee ranking)

1. Source power and lifetime including condenser optics lifetime
2. Availability of defect free masks
- 3. Reticle protection during storage, handling, and use**
4. Projection and illuminator optics lifetime and contamination
5. Resist resolution, sensitivity, and LWR
6. Optics quality for 32nm node

Information Disclosure

- **All material presented today is considered non-confidential, intended to benefit industry standards.**
- **Proceedings and minutes will be published on the ISMT public website soon after the Workshop.**